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*2/A*  
*3-29-01*  
*J. Antis*

*[Signature]* / Ruth Montalvo Date: February 1, 2001

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Customer No.: 026418

Docket No.: JG-SU-5038 / 500577.2

Applicant(s): Mohammad B. SHABANI and Shigeru OKUUCHI

Application No.:

Filed: Concurrently herewith

For: METHOD FOR ANALYZING IMPURITIES IN A SILICON SUBSTRATE  
AND APPARATUS FOR DECOMPOSING A SILICON SUBSTRATE  
THROUGH VAPOR-PHASE REACTION

Commissioner for Patents  
Washington, D.C. 20231

**PRELIMINARY AMENDMENT**

Sir:

The above-identified application is filed concurrently herewith, please  
amend the claims as follows:

**IN THE CLAIMS**

Claim 3, ✓ line 1, delete "or 2"

Claim 4, ✓ line 1, delete "or 2"

Claim 5, ✓ line 1, delete "or 2"

Claim 8, ✓ line 1, delete "or 2"

Add new claims 13 - 20.

-- 13. A method to claim 2 further comprising the steps of:

adding an acid mixture of hydrochloric acid and nitric acid to the recovered  
decomposition residue;

heating the yield to 60 - 90°C, to allow the residue to sublime; and

quantitatively analyzing the remnants by atomic absorption spectroscopy or by  
inductively coupled plasma mass spectroscopy.

*AI*  
*cont.*